

	L #	Hits	Search Text	DBs
1	L1	925	430/321.ccls.	USPA T; US-PG PUB
2	L4	10404	waveguide\$1.ti,ab.	USPA T; US-PG PUB
3	L5	73	1 and 4	USPA T; US-PG PUB
4	L6	19263 7	(polymer or organic or polymeric or photosensitiv\$6 or photopolymeri\$6 or photoresist or polymeriz\$6 or polymeris\$6 or resist).ti,ab.	USPA T; US-PG PUB
5	L7	526	4 and 6	USPA T; US-PG PUB
6	L8	166	(oxygen\$6 or deoxygen\$6 or o2 or o?sub.2) and 7	USPA T; US-PG PUB
7	L9	75	((oxygen\$6 or deoxygen\$6 or o2 or o?sub.2) same (vacuum or pressure or inert or gas)) and 7	USPA T; US-PG PUB
8	L10	40865	(partial\$4 or incomplet\$4 or full\$4) with (polymeriz\$6 or polymeris\$6 or cure\$1 or curing or harden\$4)	USPA T; US-PG PUB
9	L11	44	7 and 10	USPA T; US-PG PUB
10	L12	1133	385/129,130.ccls.	USPA T; US-PG PUB
11	L13	408	385/143,145.ccls.	USPA T; US-PG PUB
12	L14	142	12 and 6	USPA T; US-PG PUB
13	L15	15377 1	liquid.ti,ab.	USPA T; US-PG PUB

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	L #	Hits	Search Text	DBs
14	L16	39	4 and 6 and 15	USPA T; US-PG PUB
15	L17	16694 3	(photosensitiv\$6 or photopolymeri\$6 or photoresist or resist or expos\$4 or irradiat\$4 or radiat\$4).ti,ab.	USPA T; US-PG PUB
16	L18	79	13 and 17	USPA T; US-PG PUB
17	L19	66043	waveguide\$1	EPO; JPO; DERW ENT; IBM_T DB
18	L20	4612	(polymer or organic or polymeric or photosensitiv\$6 or photopolymeri\$6 or photoresist or polymeriz\$6 or polymeris\$6 or resist) and 19	EPO; JPO; DERW ENT; IBM_T DB
19	L22	68	((oxygen\$6 or deoxygen\$6 or o2 or o?sub.2) same (vacuum or pressure or inert or gas)) and 20	EPO; JPO; DERW ENT; IBM_T DB
20	L23	24	((partial\$4 or incomplet\$4 or full\$4) with (polymeriz\$6 or polymeris\$6 or cure\$1 or curing or harden\$4)) and 20	EPO; JPO; DERW ENT; IBM_T DB